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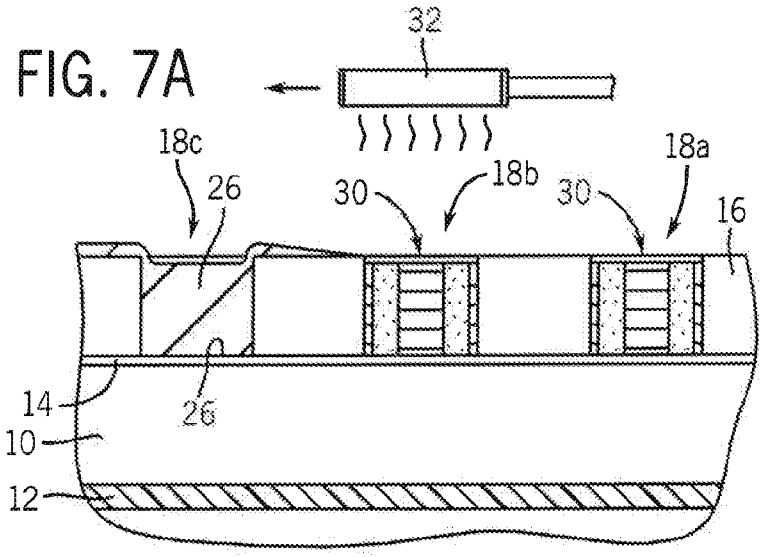
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(54) **Title**: THERMAL ANNEAL OF A BLOCK COPOLYMER FILMS WITH TOP INTERFACE CONSTRAINED TO WET BOTH BLOCKS WITH EQUAL PREFERENCE

FIG. 7A



(57) **Abstract**: Methods for fabricating sublithographic, nanoscale microstructures utilizing self-assembling block copolymer, and films and devices formed from these methods are provided.

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